

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Hojo et al.
Appl. No.	:	10/553,083
Filed	:	October 11, 2005
For	:	POSITIVE RESIST COMPOSITION AND METHOD OF FORMATION OF RESIST PATTERN
Examiner	:	C. Hamilton
Group Art Unit	:	1752

SUBMISSION WITH RCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **July 3, 2007**, and the Advisory Action mailed **October 16, 2007**, Applicants respectfully request the Examiner to enter the following amendments and consider the following remarks.

Amendments to the claims are reflected in the **listing of claims** which begins on page 2 of this paper.

Remarks begin on page 6 of this paper.